

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Pre Amended
DHAUGHFA
7-1-03

Applicants: Dr. Uwe W. Hamm,

Examiner:

Serial No:

Group Art Unit:

Filed: December 6, 2001

Date: December 6, 2001

For: **PROCESS AND DEVICE FOR IN-SITU DECONTAMINATION OF AN
EUV-LITHOGRAPHY DEVICE**

Assistant Commissioner for Patents
Washington, D.C. 20231

PRELIMINARY AMENDMENT

Sir:

Please amend the application as indicated below before calculation of the
application fees as follows:

IN THE SPECIFICATION:

Page 1:

Please replace the first paragraph as follows:

FIELD OF THE INVENTION

The invention concerns a process as well as a device for in-situ
decontamination of an EUV lithography device.

Please replace the second paragraph on Page 1 as follows:

BACKGROUND OF THE INVENTION

EUV lithography devices are used in the manufacturing of semiconductor
components, e.g. integrated circuits. Lithography devices, which are
operated in the wavelength range of extreme ultraviolet (e.g. at a

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